

Amendments to the Specification:

Please replace the paragraph beginning at page 25, line 22 with the following amended paragraph:

Reference numeral 606 indicates a coil shape electrode (antenna) and 609 indicates a quartz ~~substrate~~ plate. Dielectric magnetic field is generated by supplying electric power from RF power source 605 to an electrode 606 and is applied into the chamber through the quartz ~~substrate~~ plate. Electrons are accelerated and plasma is generated according to the dielectric magnetic field.

Please replace the paragraph beginning at page 26, line 6 with the following amended paragraph:

The quartz ~~substrate~~ plate 609 is exposed to the inside of the chamber in the ICP etching apparatus shown in FIG. 6. And  $\text{BO}_x$  is attached to the surface exposed to the inside of the chamber when  $\text{BCl}_3$  or the like is used as an etching gas. According to the cleaning method of the present invention, the  $\text{BO}_x$  attached to the quartz ~~substrate~~ plate can be removed and decline in plasma density inside the chamber due to the  $\text{BO}_x$  can be suppressed.